

SUBSTRATE CLEANING DEVICE

ABSTRACT

5 A substrate cleaning device that facilitates control of the amount of liquid supplied to a substrate and reduces adverse influences of the liquid supplied to a bearing part on the substrate is provided. The substrate cleaning device includes: a holding part 100 that has a bearing part 40 configured to rotatably hold a cleaning member 200 for cleaning a substrate W; a first supply part 110 that has at least a part provided inside the
10 holding part and supplies a first liquid into the cleaning member 200 through the inside of the holding part; and a second supply part 120 that supplies a second liquid to the bearing part 40.

15 FIG. 1